

L Number	Hits	Search Text	DB	Time stamp
99	5889	(sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 07:57
100	12	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:02
101	50	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)) same (humidity rh))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:02
102	30	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:03
103	18	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!)) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:03
104	58	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) same haze)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:55
105	6	("4019887" "4100330" "4144684" "4188444" "4385806" "4485146").PN.	USPAT	2002/12/27 08:46
106	0	gb-705934-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:55
107	0	uk-705934-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:55
108	14	"705934"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:55
109	79	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:20
110	61	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:22
111	18	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)) not (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:23
112	7048	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:30
113	2297	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 10:16

114	17	((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:57
115	103	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 10:16
116	99	(((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing)))) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity rh!)) (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)) same (humidity rh!)) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity rh!)) (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((humidity rh!)) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same ((relative near humifity rh!))) (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) same haze)) (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)) (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)) (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near mean near square near surface near roughness)) not (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))) ((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition deposited deposit depositing))) and (alkylchlorosilane dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2 CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3 near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si) (ch?sub.3 near si near cl?sub.3))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 10:17
-	276323	polysiloxane organopolysiloxane polyorganosiloxane polydiorganosiloxane diorganopolysiloxane silicone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/01/04 06:57
-	6	((("5846649") or ("5618619") or ("5508368") or ("6077569") or ("6416816") or ("6245387"))).PN.	USPAT	2002/12/19 12:24
-	0	wo-0025938-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:24
-	0	wo-00025938-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:24
-	0	wo-25938-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:31
-	0	wo-025938-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:31
-	0	wo-00025938.ap.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:32

-	0	2000wo-0025938.ap.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:33
-	131	"25938"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:36
-	7761	428/426,446,447.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:37
-	161140	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:45
-	1327	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating) and haze	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:49
-	9620	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating) and (humidity rh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:49
-	145	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating) and haze)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:50
-	352	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating) and (humidity rh))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:02
-	47	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:47
-	256721	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:46
-	7037	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and (surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:28
-	2839	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and haze	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:49
-	19608	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and (humidity rh)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 07:55
-	193	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and (surface near roughness))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:50
-	258	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and haze)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 08:20
-	605	428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating) and (humidity rh))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:50

-	16	(428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:50
-	61	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:21
-	15	((428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))) not (((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:51